Test of GEM produced by Fujikura company

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TPC(Time Projection Chamber)



We can reconstruct track by using three parameter r, $r\phi$ and Z.

How to decide these parameter? To measure

- r φ:Position of charge signal COG(Center value Of Gravity)
- Z:Drift time of electron



GEM is a one of the candidate for gas multiplication.

 GEM(Gas Electron Multiplier)
When (high) voltage difference is applied between upper and lower electrodes, electrons are multiplied.

We can read charge of electrons.

This figure and two pictures show the GEM produced by Scienergy company.



Test Chamber

- We measure gain of new GEM.
- The chamber is filled with P10 gas(Ar:CH4=90:10).
- X-ray interact with gas atom in drift region, and ionized electrons start to drift to GEM.



New GEM produced by Fujikura company

This figure shows new method of making a hole.



Fuiikura GEM and Scienergy GEM **Fujikura GEM** 70 µm F-Side Zµm Hole size of F-side is 50 µ m bigger than B-side. **B**-Side 60 µ m Scienergy GEM 70 µ m $5 \mu m$ Hole size is same at both 50 µ m side. 70 µ m

Hole of Scienergy GEM is made by Co2 laser(thermal process), but Fujikura GEM is made by UV-YAG laser. So these GEMs have different hole size.

We have to check performance of Fujikura GEM.

Experimental data

Energy spectrum of X-ray



Energy(ADC channel)

We compared Fujikura GEMs and Scienergy GEMs.

We checked Fujikura GEMs have enough gain .





Next

- We checked gain of Fujikura GEM that is made by UV-YAG laser technology.
- UV-YAG laser technology is useful method.



- We want to apply this technology to produce gate GEM.
- Aperture of Gate GEM have to be high, because we want to get good transmission.
- UV-YAG laser technology has high accuracy of making a hole. We expect that we can get high aperture of gate GEM.

Gating system by GEM

When electrons are multiplied, many ions are produced and go back to drift region and make ion disc.

These ions have to be stopped by using gate.

Beam pulse structure



Close



Direction of Electric field is reversed. Ions are stopped by gate GEM.



Gate GEM produced by Fujikura company



• Pitch 330µm

1			
hole size(µm)	pitch (µm)	aperture ratio (%)	
300	390	53.60946746	
300	360	62.91666667	
300	330	74.87603306	
300	300	90.6	

This sample is in this case.

Performance of Gate GEM

- Ions can be stopped easily.
- Gate must provide good electron transmission, but it is not easy to improve.
- Making large aperture is a one of solution.
- The feature of precision process by YAG laser can make a bigger hole.
- We need to understand gate performance not only form data also from simulation.

Measurement of the electron transmission



Collection efficiency

and Extraction efficiency

Collection efficiency







n_{Hole} : The number of electrons that go into the hole

nDrift or Transfer : The number of electron that is in drift region or transfer region **nTransfer or Induction** : The number of electrons that go out of the hole

Transmission

Electron transmission is given by this equation

$$T = \frac{n_{Transfer \text{ or Induction}}}{n_{Drift \text{ or Transfer}}} (= C \times E)$$

Aperture of Gate GEM have to be high, because we want to get good transmission.

UV-YAG laser technology has high accuracy of making a hole. We expect that we can get high aperture of Gate GEM.



We will check how we can apply this technology of Fujikura company.



- Do Fujikura Gate GEMs have enough electron transmission?
- We have to study effect of different hole size at each side.
- Next page is result of Philippe's simulation.

Philippe's simulation for Fujikura Gate GEM

pitch 140um/330um 20um diff. in diam.



This graph shows Philippe's simulation for Fujikura gate GEM.

Red line means upper electrode is F-side. Green line means upper electrode is Bside.

In this case is using T2K gas.

According to this result, both side is not so different.

We have to compare experimental data and this result.

Summary

- Fujikura GEM have enough gain.
- UV-YAG laser technology has high accuracy of making a hole.
- We apply this technology to make gating system.

• We will measure the transmission of new gate soon, and compare the data to simulation result to understand performance of gate GEM.

Thank you!



Back up

Data2





Gain of comparison condition⁵ is bigger than comparison condition④.

Comparison condition





• Upper electrode :Fside ■ Upper electrode :B-side

Data3 Event \$55354 \$5

s5f3s4 s5b3s4.325v



Gain of comparison condition⁶ is bigger than comparison condition⁷.

Comparison condition





◆ Upper electrode :F-side ■ Upper electrode :B-side

Data4



Gain of comparison condition⁽⁹⁾ is bigger than comparison condition⁽⁸⁾.

Comparison condition



Gain



• Upper electrode :F-side

Upper electrode :B-side